

Atty. Dkt. No. 039153-0310 (F0797)

Amendments to the Specification:

Please amend the specification as follows:

Please replace paragraph number [0001], with the following rewritten paragraph:

[0001] The present application is related to U.S. Application Serial No. 09/819,692 (Atty Dkt. No. 39153-403 (F0943)) by Okoroanyanwu et al., filed March 28, 2001, entitled "PROCESS FOR PREVENTING DEFORMATION OF PATTERNED PHOTORESIST FEATURES BY ELECTRON BEAM STABILIZATION;" U.S. Application Serial No. 09/820,143 (Atty Dkt. No. 39153-405 (F0945)) by Okoroanyanwu et al., filed March 28, 2001, entitled "IMPROVING SEM INSPECTION AND ANALYSIS OF PATTERNED PHOTORESIST FEATURES;" U.S. Application Serial No. 09/819,344 (Atty Dkt. No. 39153-406 (F1061)) by Okoroanyanwu et al., filed March 28, 2001, entitled "PROCESS FOR REDUCING THE CRITICAL DIMENSIONS OF INTEGRATED CIRCUIT DEVICE FEATURES;" U.S. Application Serial No. 09/819,342 (Atty Dkt. No. 39153-403 (F0942)), by Shields et al., filed March 28, 2001, entitled "PROCESS FOR FORMING SUB-LITHOGRAPHIC PHOTORESIST FEATURES BY MODIFICATION OF THE PHOTORESIST SURFACE;" and U.S. Application Serial No. 09/819,343 (Atty Dkt. No. 39153-298 (F0785)) by Gabriel et al., entitled "SELECTIVE PHOTORESIST HARDENING TO FACILITATE LATERAL TRIMMING," and all assigned to the Assignee of the present application.